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Concl'd.*

6. (New) The method as claimed in claim 4, including the steps of applying a photomask of N⁺ dopant and implanting N⁺ dopant to form the N⁺ source region above the P⁻ well.

7. (New) The method as claimed in claim 4, including the steps of producing a photoresist prior to etching the N⁺ source region and removing the photoresist after the P⁺ well is formed.

8. (New) The method as claimed in claim 4, wherein the glass layer is comprised of boro-phospho silicate glass.

REMARKS

This Preliminary Amendment is being filed concurrently with a new U.S. application. Consideration and allowance of the application, including newly presented claims 3-8, are respectfully requested.

Early and favorable action is earnestly requested.

Respectfully submitted,

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